

SUBSTITUTE SPECIFICATION CLEAN VERSION

METHOD AND APPARATUS  
FOR AUTOMATIC APPLICATION AND  
MONITORING OF A STRUCTURE TO BE  
APPLIED ONTO A SUBSTRATE

ABSTRACT OF THE DISCLOSURE

A method and apparatus are provided for automatic application and monitoring of a structure to be applied onto substrate. A plurality of cameras positioned around an application facility are utilized to monitor the automatic application of a structure on a substrate by means of a stereometry procedure. Three-dimensional recognition of a reference contour position results in the overlapping area to be used for gross adjustment of the application facility prior to applying the structure.